

**Notice of References Cited**

Application/Control No.

09/838,513

Applicant(s)/Patent Under

Reexamination

CHEN ET AL.

Examiner

Julio J. Maldonado

Art Unit

2823

Page 1 of 1

**U.S. PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Name	Classification
*	A	US-5,937,325	08-1999	Ishida, Emi	438/655
*	B	US-6,514,859 B1	02-2003	Erhardt et al.	438/664
	C	US-			
	D	US-			
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	K	US-			
	L	US-			
	M	US-			

**FOREIGN PATENT DOCUMENTS**

*		Document Number Country Code-Number-Kind Code	Date MM-YYYY	Country	Name	Classification
	N					
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	S					
	T					

**NON-PATENT DOCUMENTS**

*		Include as applicable: Author, Title Date, Publisher, Edition or Volume, Pertinent Pages)
*	U	Mouroux, Alette; The Reactive Formation of TiSi <sub>2</sub> in the Presence of Refractory Metals (from V to W), Royal Institute of Technology, Department of Electronics, Stockholm 1,999.
	V	
	W	
	X	

\*A copy of this reference is not being furnished with this Office action. (See MPEP § 707.05(a).)  
Dates in MM-YYYY format are publication dates. Classifications may be US or foreign.